*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

In re application of: Hill et al.

Application No.: NEW

Filed: HEREWITH

Title: METHOD OF FABRICATING LOW DIELECTRIC CONSTANT DIELECTRIC FILMS

Attorney Docket No.: NOVLP050D1/NVLS-000682D1

Examiner: UNASSIGNED

Group: UNASSIGNED

**INFORMATION DISCLOSURE STATEMENT**
**37 CFR §§1.56 AND 1.97(b)**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449 may be material to examination of the above-identified patent application. Applicants submit the list of these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application. The above-identified application is a Divisional of prior application U.S. Patent Application No. 10/171,289. This prior application is being relied upon for an earlier filing date under 35 U.S.C. § 120. Because the listed references were either cited by the PTO, or submitted to the PTO in the prior application, under 37 CFR § 1.98(d) Applicants submit that copies need not be provided.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP050D1).

Respectfully submitted,
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| Form 1449 (Modified) | Atty Docket No. NOVLP050D1/NVLS-000682D1 | Application No.: NEW |
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| **Information Disclosure Statement By Applicant** | Applicant: Hill et al. | |
| (Use Several Sheets if Necessary) | Filing Date HEREWITH | Group UNASSIGNED |

**U.S. Patent and Published Documents**

| Examiner Initial | No. | Patent No. | Date | Patentee | Class | Sub-class | Filing Date |
|---|---|---|---|---|---|---|---|
| | A1 | 6,329,062 | 12/11/01 | Gaynor | | | |
| | A2 | 6,268,276 | 7/31/01 | Chan et al. | | | |
| | A3 | 6,177,329 | 1/23/01 | Pang | | | |
| | A4 | 5,920,790 | 07/99 | Wetzel et al. | | | |
| | A5 | 2003/0119307 | 06/03 | Bekiaris et al. | | | |

**Foreign Patent or Published Foreign Patent Application**

| Examiner Initial | No. | Document No. | Publication Date | Country or Patent Office | Class | Sub-class | Translation | |
|---|---|---|---|---|---|---|---|---|
| | | | | | | | Yes | No |
| | B1 | WO95/07543 | 03/16/95 | WIPO | | | X | |
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**Other Documents**

| Examiner Initial | No. | Author, Title, Date, Place (e.g. Journal) of Publication |
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| | C1 | R.D. Miller et al., "Phase-Separated Inorganic-Organic Hybrids for Microelectronic Applications," MRS Bulletin, October 1997, Pages 44-48 |
| | C2 | Jin et al., "Nanoporous Silica as an Ultralow-*k* Dielectric," MRS Bulletin, October 1997, Pages 39-42 |
| | C3 | Cleemput et al., "Dielectric Films With Low Dielectric Constants," Application Serial No.: 09/727,796, filed November 30, 2000, |
| | C4 | Asoh et al., "Fabrication of Ideally Ordered Anodic Porous Alumina with 63 nm Hole Periodocity Using Sulfuric Acid," J. Vac. Sci. Technol. B 19(2), Mar/Apr 2001, Pages 569-572 |
| | C5 | Asoh et al., "Conditions for Fabrication of Ideally Ordered Anodic Porous Alumina Using Pretextured AI," Journal of the Electrochemica Society, 148 (4) B152-B156 (2001) Pages B152-B156 |
| | C6 | Holland et al., "Nonlithographic Technique for the Production of Large Area High Density Gridded Field Sources," J. Vac. Sci. Technol. B 17(2), Mar/Apr. 1999, Pages 580-582 |
| | C7 | Masuda et al. "Highly Ordered Nanochannel-Array Architecture in Anodic Alumina," App. Phys. Lett. 71(19), November 1997, Pages 2770-2772 |

| Form 1449 (Modified)<br><br>**Information Disclosure Statement By Applicant**<br><br>(Use Several Sheets if Necessary) | Atty Docket No.<br>NOVLP050D1/NVLS-000682D1<br>Applicant:<br>Hill et al.<br>Filing Date<br>HEREWITH | Application No.:<br>NEW<br><br><br><br>Group<br>UNASSIGNED |
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| | C8 | Clube et al., "White Paper from Holotronic Technologies SA; downloaded from www.hdotronic.com/whitepaper/fine-patt.pdf on March 12, 2002 |
| | C9 | Meli et al., "Self-Assembled Masks for the Transfer of Nanometer-Scale Patterns into Surfaces: Characterization by AFM and LFM", Nano Letters, Vol. 2, No. 2, 2002, 131-135 |
| | C10 | "Shipley Claims Porous Low K Dielectric Breakthrough," Press Release March 17, 2003. |

| Examiner | Date Considered |
|---|---|
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.